U.S. PATENT DOCUMÉNTS			Notice of Refe	rences Cited		Application No.  OB-84667 Ko  Examiner Group Art Unit  George Goud Year 1763 Page (of 1					
A  B  C  D  P  FOREIGN PATENT DOCUMENTS  *  DOCUMENT NO. DATE COUNTRY NAME  N  SC-114, 355 9-8-81 Japan Unit  N  N  N  N  N  DOCUMENT (Including Author, Title, Source, and Pertlinent Pages)  U  N  NON-PATENT DOCUMENTS  *  DOCUMENT (Including Author, Title, Source, and Pertlinent Pages)  U  N  P  C  N  N  N  DOCUMENT (Including Author, Title, Source, and Pertlinent Pages)  U  N  N  C  N  N  N  N  N  N  N  N  N  N	U.S. PATENT DOCUMENTS										
A   B   C   C   C   C   C   C   C   C   C	Ľ	1	DOCUMENT NO.	DATE			NAME		CLASS	SUBCLASS	
C D D C C D D C C C C C C C C C C C C C	L	Α									
DOCUMENT (including Author, Title, Source, and Pertinent Pages)  Whether it is a solid process of the professional	L	В							<del>                                     </del>		
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GO N 56-114, 355 9-8-8/ Japan 491 0 P 0 R S T  NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Nechanisms of High PSG/ Silven Dioxid GELOCITY SAPPLED AND SOURCE AND PSG/ Silven Dioxid GELOCITY SAPPL. PAGENT S	L	c							+	<del> </del>	
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GO N 56-114, 355 9881 Jayan Unit P O O R S T  NON-PATENT DOCUMENTS  * DOCUMENT (including Aurinor, Title, Source, and Pertinent Pages)  U Nechanisms of High PSG/Silvan Dioxid Gottant T, (1991); They are they are polyment for the pages of the page of the page of the pages	l	D				<del></del>			+		
G H II J K L DOCUMENT NO. DATE COUNTRY NAME G N 56-114, 355 9-8-81 Japan 4032  P Q R S T  NON-PATENT DOCUMENTS  *  NON-PATENT DOCUMENTS  *  DOCUMENT (including Aurinor, Title, Source, and Pertinent Pages)  U Nechanisms of High PSG/ Silver Dioxid Selantine External of Apply Polyment Fluorotantor Plasma Japan Polyment Page Japan School of Appl. Ph	Γ	Ε							-		
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME OF SOCIETY OF SOCI	Γ	F									
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME OF SOURCE OF SOUR	Γ	G							-		
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GROUP  N 56-114, 355 9-8-81 Japan 491   P O R S S S S S S S S S S S S S S S S S S	Γ	н							+	<del> </del> -	
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GOOD  N 56-114, 355 9-8-81 Japan Upg.  P  Q  R  S  T    NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silver Dioxical Selactive Etching In a Highly Polyment Pages)  Fluorocartor Plasma I Japan Polyment Pages  & Theorocartor Plasma I Japan Polyment Pages  # 130(7)		1							<del> </del>		
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GA  N 56-114, 355 9-8-81 Japan you  P  Q  NN 56-114, 355 9-8-81 Japan you  NON-PATENT DOCUMENTS  * DOCUMENT (including Aurinor, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silven Deviced Selection Relation Plasma of Jan Japan Polyment  Fluorocarton Plasma of Jan Japan Polymen  But I; (19911); I Kegani et al., pp. 1556		J							<del> </del>		
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GR.  N 56-114, 355 9-8-81 Japan Upili  P  Q  R  S  T    NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silver Blooked  Selective Etching In a Hyper Polymen  Fluorocartor Plasma Japan Polymen  of The Source of Th		к		<del>                                     </del>							
FOREIGN PATENT DOCUMENTS  * DOCUMENT NO. DATE COUNTRY NAME GA  N 56-114, 355 9-8-81 Jayan Upg  P  Q  R  S  T    NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanians of High PSG/ Salion Dioxid Selective Etching In a Highly Polyment  Fluorocarbon Plasma Jayan Polyment  Plast I; (1991); I regani et al., pp. 1556		L			·					<u> </u>	
* DOCUMENT NO. DATE COUNTRY NAME GA  N 56-114 355 9-8-81 Japan Upili  P  Q  NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSF/ Silver Dioxical Selective Etching In a Higher Polyment Fluorocarton Plasma", Jpn J. Appl. Ph  Part I; (1991); I Kegani et al., pp 1556;  30(7)		м									
* DOCUMENT NO. DATE COUNTRY NAME GA  N 56-114 355 9-8-81 Japan Upili  P  Q  NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSF/ Silver Dioxical Selective Etching In a Higher Polyment Fluorocarton Plasma", Jpn J. Appl. Ph  Part I; (1991); I Kegani et al., pp 1556;  30(7)											
N 56-114, 355 9-8-81 Japan Yolg  P  O  NON-PATENT DOCUMENTS  *  DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silvion Deviced Selective Etching In a Highly Polyment  Fluorocarbon Plasma I Jan J. Appl. Ph.  Part I; (19911); I Kegani et al.; pp. 1556;	* DOCUMENTAGE										
NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  "Mechanisms of High PSG/ Silver Deoxied Selective Etching In a Hegyly Polyment Fluorocarton Plasma"; Jpn J. Appl. Ph. Part I; (1991); I Kegani et al.; pp 1556;		Z	56-114 255		COON	Λ <sub>0</sub>		NAME	GLASS	SUBCLASS	
NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  "Mechanisms of that PSG/ Silven Blooked Selantine Etching In a Highly Polymen  by Fluorocarton Plasma i Jan J. Appl. Ph.  last I; (1991); I Kegani et al.; pp. 1556;  30(7)		$\dashv$	26 11 7 23 2	7-0-01		yean	-yoji				
NON-PATENT DOCUMENTS  * DOCUMENT (including Aurinor, Tirile, Source, and Pertinent Pages)  " Mechanisms of High PSG/ Silvien Deoxical Solarities Etching In a Higher Polyment Fluorocarton Plasma"; Jpn J. Appl. Ph. Part I; (1991); I Kegani et al.; pp. 1556;  30(7)							0 0				
NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  " Mechanisms of High PSG/ Silver Devoted Selective Etching In a Highly Polymer of Fluorocartor Plasma"; Jan J. Appl. Ph. Bart I; (1991); I Kegani et al., pp. 1556;  30(7)		-			·····						
NON-PATENT DOCUMENTS  * DOCUMENT (including Aurinor, Titie, Source, and Pertinent Pages)  " Mechanisms of High PSG/ Silver Deviced Selective Etching In a Highly Polymen Fluorotanton Plasma", Jpn In Appl. Photostat I; (1991); I Kegani et al.; pp 1556;  30(7)	+	-									
NON-PATENT DOCUMENTS  * DOCUMENT (including Aurinor, Title, Source, and Pertinent Pages)  "Mechanisms of High PSG/ Silvion Dioxid Selactive Etching In a Highly Polyment Fluorocarbon Plasma"; Jpn J. Appl. Ph. Bort I; (19911); I Kegani et al.; pp. 1556;  30(7)	-	-									
NON-PATENT DOCUMENTS  * DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silvion Deoxid Selartine Etching In a Highly Polymen  Fluorocarton Plasma " Jpn In Appl. Ph  Part I; (1991); I Kegani et al., pp 1556;  30(7)	-+	-									
DOCUMENT (including Author, Title, Source, and Pertinent Pages)  U Mechanisms of High PSG/ Silver Debxiel Selantine Etching In a Highly Polymen  Fluorocarton Plasma " Jpn J. Appl. Ph  Bart I; (1991); I Kegani et al.; pp 1556;  30(7)											
U Mechanisms of High PSG/ Silicon Deoxid Selartire Etching In a Highly Polyment Fluorocarton Plasma", Jpn J. Appl. Phylost I; (19911); I Kegani et al.; pp 1556; 30(7)	*	Т									
Selective Etching In a Highly Polymer Fluorocarton Plasma"; Jon J. Appl. Ph Bort I; (1991); I Kegani et ol; pp 1556; 30(7)	+	+									
80(7) (1991); I Kegani et ol; pp 1556;		" Mechanisms of High PSG/ Silicon Deoxida									
30(7)		6	Jan Jan Hapl. Mys								
x	1	١	30(7) 1(1991) + Regari ettal, pp 1556 (;								
	,	<b>,</b>									

\* A copy of this reference is not being funished with this Office action. (See Manual of Patent Examining Procedure, Section 707.05(a).)